

Electronic Version v18 Stylesheet Version v18.0

> Title of Invention

HIGH PRESSURE PROCESSING CHAMBER FOR SEMICONDUCTOR SUBSTRATE

Application Number:

09/912844

Confirmation Number:

5915

First Named Applicant:

Thomas Haverstock

Attorney Docket Number:

Search string:

( 6521466 or 6541278 or 6546946 or 6550484

or 6558475 or 6561213 or 6561220 or 6561481

or 6561767 or 6564826 or 5217043 or

20020001929 ).pn.

## **US Patent Documents**

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

					[10-4]	Class	Subclass
init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Juociass
	1	6521466	2002-02-18	Castrucci	B1		
	2	6541278	2003-04-01	Morita et al.	B1		
		6546946	2003-04-15	Dunmire	B1		
		6550484	2003-04-22	Gopinath et al.	B1		
1	5	6558475	2003-05-06	Jur et al.	B1		
	<u> </u>	6561213	2003-05-13	Wang et al.	B1	<u> </u>	
	7	6561220	2003-05-13	McCullough et al.	B1	<u> </u>	
7	8	6561481	2003-05-13	Filonczuk	B1	]	
	9	6561767	2003-05-13	Biberger et al.	B1	]	
	\ <u></u>	6564826	2003-05-20	Shen	B1	]	
	<u> </u>		1993-06-08	Novakovi	ī	-	
~	11	5217043	1993-00-00		<del></del>		

## **US Published Applications**

Note: Applicant is not required to submit a paper copy of cited US Published Applications

					1	Close	Subclass
init	Cite.No.	Pub. No.	Date			Class	Subclass
		20020001929	2002-01-03	Biberger et al.	A1		

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Examiner Name	Date
	11-21-03

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## ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18
Stylesheet Version v18.0

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Application Number:

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First Named Applicant:

Maximilian Biberger

Attorney Docket Number:

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( 5900107 or 5904737 or 5932100 or 5934991 or 5981399 or 5989342 or 6005226 or 6017820 or 6029371 or 6037277 or 6053348 or 6056008 or 6077053 or 6082150 or 6085935 or 6097015 or 6128830 or 6145519 or 6159295 or 6164297 or 6203582 or 6216364 or 6239038 or 6241825 or 6251250 or 6277753 or 6286231 or 6305677 or 6334266 or 6344174 or 6388317 or 6389677 or 6418956 or 6436824 or 6454945 or

6464790 ).pn.

**US Patent Documents** 

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init	Cite.No.	Patent No.	Date	Patentee	Kind				
	1	5900107	1999-05-04	Murphy et al.					
P	2	5904737	1999-05-18	Preston et al.					
F	3	5932100	1999-08-03	Yager et al.					
F	4	5934991	1999-08-10	Rush					
N	5	5981399	1999-11-09	Kawamura et al.					
	6	5989342	1999-11-23	Ikeda et al.					
	7	6005226	1999-12-21	Aschner et al.					
	8	6017820	2000-01-25	Ting et al.					
	9	6029371	2000-02-29	Kamikawa et al.	]				
F	10	6037277	2000-03-14	Masakara et al.					
	11	6053348	2000-04-25	Morch	]				
7	12	6056008	2000-05-02	Adams et al.	]				
7	13	6077053	2000-06-20	Fujikawa et al.					

**Subclass** 

Class

V	14	6082150	2000-07-04	Stucker	
	15	6085935	2000-07-11	Malchow et al.	
	16	6097015	2000-08-01	McCullough et al.	
F	17	6128830	2000-10-10	Bettcher et al.	
F	18	6145519	2000-11-14	Konishi et al.	
Y	19	6159295	2000-12-12	Maskara et al.	
1	20	6164297	2000-12-26	Kamikawa	
1	21	6203582	2001-03-20	Berner et al.	B1
~	22	6216364	2001-04-17	Tanaka et al.	B1
T	23	6239038	2001-05-29	Wen	B1
V	24	6241825	2001-06-05	Wytman	B1
L	25	6251250	2001-06-26	Keigler	B1
	26	6277753	2001-08-21	Mullee et al.	B1
1	27	6286231	2001-09-11	Bergman et al.	B1
	28	6305677	2001-10-23	Lenz	B1
	29	6334266	2002-01-01	Moritz et al.	B1
۲	30	6344174	2002-02-05	Miller et al.	B1
L.	31	6388317	2002-05-14	Reese	B1
	32	6389677	2002-05-21	Lenz	B1
	33	6418956	2002-07-16	Bloom	B1
1	34	6436824	2002-08-20	Chooi et al.	B1
1	35	6454945	2002-09-24	Weigl et al.	B1
1	36	6464790	2002-10-15	Shertinsky et al.	B1

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**Application Number:** 

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(5193560 or 5195878 or 5213485 or 5221019 or 5222876 or 5224504 or 5236669 or 5240390 or 5243821 or 5246500 or 5251776 or 5280693 or 5285352 or 5288333 or 5339844 or 5370741 or 5412958 or 5433334 or 5447294 or 5503176 or 5505219 or 5509431 or 5571330 or 5589224 or 5621982 or 5629918 or 5644855 or 5649809 or 5656097 or 5669251 or 5702228 or 5706319 or 5746008 ).pn.

#### **US Patent Documents**

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				Datastas	Kind	Class	Subclass
init	Cite.No.	Patent No.	Date	Patentee	Killu		
V	1	5193560	1993-03-16	Tanaka et al.			
	2	5195878	1993-03-23	Sahiavo et al.	ļ		
	3	5213485	1993-05-25	Wilden	Į		
	4	5221019	1993-06-22	Pechacek	į		
IV	5	5222876	1993-06-29	Budde	ļ	•	
	6	5224504	1993-07-06	Thompson et al.	ļ		
1	7	5236669	1993-08-17	Simmons et al.	Ţ		
1	8	5240390	1993-08-31	Kvinge et al.	Ţ		
	9	5243821	1993-09-14	Schuck et al.	Ţ		
	10	5246500	1993-09-21	Samata et al.	ļ		
1	11	5251776	1993-10-12	Morgan Jr. et al.	_[		
	12	5280693	1994-01-25	Heudecker			
	13	5285352	1994-02-08	Pastore et al.	1		
				T	ı		

	<i>.</i>			1
الد	14	5288333	1994-02-22	Tanaka et al.
	15	5339844	1994-08-23	Stanford Jr. et al.
	16	5370741	1994-12-06	Bergman
	17	5412958	1995-05-09	liiff et al.
	18	5433334	1995-07-18	Reneau
	19	5447294	1995-09-05	Sakata et al.
H	20	5503176	1996-04-02	Dunmire et al.
1	21	5505219	1996-04-09	Lansberry et al.
H	22	5509431	1996-04-23	Smith, Jr. et al.
F	23	5571330	1996-11-05	Kyogoku
H	24	5589224	1996-12-31	Tepman et al.
1	<u> </u>	5621982	1997-04-22	Yamashita et al.
-	26	5629918	1997-05-13	Ho et al.
-	1	5644855	1997-07-08	McDermott et al.
1	28	5649809	1997-07-22	Stapelfeldt
	29	5656097	1997-08-12	Olesen et al.
H	30	5669251	1997-09-23	Townsend et al.
14	31	5702228	1997-12-30	Tamai et al.
1	7 32	5706319	1998-01-06	Holtz
1	7 33	5746008	1998-05-05	Yamashita et al.
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Electronic Version v1 8

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P	3	6546946	2003-04-15	Dunmire	81		
$\overline{A}$	4	6550484	2003-04-22	Gopinath et al.	81		
Y	S	6558475	2003-05-06	Jur et al.	BI		
F	6	6561213	2003-05-13	Wang et al.	81		
P	7	6561220	2003-05-13	McCullough et al.	81		!
P	6	6561481	2003-05-13	Filonczuk	BI		
P	9	6561767	2003-05-13	Biberger et al.	81		
P	10	6564826	2003-05-20	Shen	BI		
P	11	5217043	1993-06-08	Novakovi			

**US Published Applications** 

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N	init Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subdass	
1		20020001929	2002-01-03	Biberger et al.	Αl			

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#### Signature

Examiner Name	Date
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( 2617719 or 2625886 or 3744660 or 3968885 or 4029517 or 4091643 or 4245154 or 4341592 or 4355937 or 4367140 or 4406596 or 4422651 or 4474199 or 4522788 or 4549467 or 4592306 or 4601181 or 4626509 or 4670126 or 4682937 or 4693777 or 4749440 or 4778356 or 4789077 or 4823976 or 4825808 or 4827867 or 4838476 or 4865061 or 4879431 or 4917556 or 4924892 or 4951601 or 4960140 or 4983223 or 5011542 or 5044871 or 5062770 or 5071485 or 5105556 or 5167716 or 5169296 or 5169408 or 5186718 or 5188515 or 5190373 or 5191993 ).pn.

#### **US Patent Documents**

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
M	1	2617719	1952-11-11	C. R. Stewart			
F	2	2625886	1953-01-20	Browne	ı		
1	3	3744660	1973-07-10	Gaines et al.			
N	4	3968885	1976-07-13	Hassan et al.			
N	5	4029517	1977-06-14	Rand			
V	6	4091643	1978-05-30	Zucchini			
M	7	4245154	1981-01-13	Uehara et al.			
V	8	4341592	1982-07-27	Shortes et al.			
1	9	4355937	1982-10-26	Mack et al.			
1	10	4367140	1983-01-04	Wilson			
1	11	4406596	1983-09-27	Budde			
					I		

. 11	0	4400054	1983-12-27	Platts
ᆚ	12	4422651		Blaudszun
<u>니</u>	13	4474199	1984-10-02	Sitek et al.
	14	4522788	1995-06-11	
	15	4549467	1985-10-29	Wilden et al.
<u> </u>	16	4592306	1986-06-03	Gallego
<u> </u>	17	4601181	1986-07-22	Privat
V	18	4626509	1986-12-02	Lyman
M	19	4670126	1987-06-02	Messer et al.
*	20	4682937	1987-07-28	Credle, Jr.
W	21	4693777	1987-09-15	Hazano et al.
M	22	4749440	1988-06-07	Blackwood et al.
N	23	4778356	1988-10-18	Hicks
N	24	4789077	1988-12-06	Noe
V	25	4823976	1989-04-25	White, III et al.
V	26	4825808	1989-05-02	Takahashi et al.
V	27	4827867	1989-05-09	Takei et al.
F	28	4838476	1989-06-13	Rahn
1	29	4865061	1989-09-12	Fowler et al.
N	30	4879431	1989-11-07	Bertoncini
7	31	4917556	1990-04-17	Stark et al
V	32	4924892	1990-05-15	Kiba et al.
V	33	4951601	1990-08-28	Maydan et al.
V	34	4960140	1990-10-02	Ishijima et al.
~	35	4983223	1991-01-08	Gessner
~	36	5011542	1991-04-30	Weil
1	37	5044871	1991-09-03	Davis et al.
~	38	5062770	1991-11-05	Story et al.
F	39	5071485	1991-12-10	Matthews et al.
~	40	5105556	1992-04-21	Kurokawa et al.
1	41	5167716	1992-12-01	Boitnott et al.
-	42	5169296	1992-12-08	Wilden
F	43	5169408	1992-12-08	Biggerstaff et al.
1	44	5186718	1993-02-16	Tepman et al.
	45	5188515	1993-02-23	Hom
1	46	5190373	1993-03-02	Dickson et al.
	47	5191993	1993-03-09	Wanger et al.
	<u> </u>	_!	<u></u>	

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Non US Patent and Publication references shall be filed under a separate paper transmittal. The current electronic filing contains part 1 out of a total of 4 electronic filings.

Examiner Name	Date
	11-26-2003

2000-03-14

2000-04-25

2000-05-02

2000-06-20

2000-07-04

2000-07-11

2000-08-01

2000-10-10

2000-11-14

2000-12-12

2000-12-26

2001-03-20

2001-04-17

2001-05-29

2001-06-05

2001-06-26

2001-08-21

2001-09-11

2001-10-23

2002-01-01

2002-02-05

2002-05-14

2002-05-21

2002-07-16

2002-08-20

2002-09-24

2002-10-15

Non US Patent and Publication references shall be filed under a separate paper transmittal.

Masakara et al.

Morch

dams et al

Fullkawa et al.

Stucker

Malchow et al.

McCullough et al.

Bettcher et al.

Konishi et al.

Maskara et al.

Kamikawa

Berner et al.

Tanaka et al.

Wytman

Kelpler

Mullee et al.

Bergman et al.

Lenz

Moritz et al.

Miller et al.

Reese

Lenz

Chool et al.

Weigl et al.

Shertinsky et al.

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Page 1 of 3

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7	7	6005226	1999-12-21	Aschner et al.	<u> </u>		
F	•	6017820	2000-01-25	Ting et zi.	7		
T	9	6029371	2000-02-29	Kamikawa et al.	7		
			i		7		

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T	7	5236669	1993-08-17	Simmons et al.	]		
N	В	5240390	1993-08-31	Kvinge et al.	]		
N	9	5243821	1993-09-14	Schuck et al.	]		
R	10	\$246500	1993-09-21	Samata et al.	1		

1993-10-12 11 5251776 Morgan fr. et al. 1994-01-25 5280693 Heudecker 1994-02-08 Pastore et al. 13 5285352 5288333 1994-02-22 Tanaka et al. 5339844 1994-08-23 Stanford jr. et al. 15 16 5370741 1994-12-06 Bergman 5412958 1995-05-09 Mill et al. 18 \$433334 1995-07-18 Renezu 5447294 1995-09-05 Sakata et al. Dunmire et al. 20 5503176 1996-04-02 5505219 1996-04-09 Lansberry et al. 5509431 1996-04-23 Smith, jr. et al. 22 23 5571330 1996-11-05 Kyogoku 1 5589224 Tepman et al. 1996-12-31 75 5521982 1997-04-22 Yamashtta et al. 5629918 1997-05-13 Ho et ai. 5644855 1997-07-08 McDermott et al 28 5649809 1997-07-22 Stapelfeldt 5656097 1997-08-12 Olesen et al. 30 5669251 1997-09-23 Townsend et al. 5702228 1997-12-30 Tamal et al. 1998-01-06 5706319 Holtz 32 33 5746008 1998-05-05 Yamashita et al

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Page 1 of 3

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Information Disclosure Statem

Page 3 of 3



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1982-07-27

1982-10-26

1983-01-04

1983-09-27

Shortes et al.

Mack et al.

Budde

ELECTRONIC	INFORMATION	DISCLOSURE STATEMENT

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First Named Applicant: Maximilian Biberger Attorney Docket Number:

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4917556 or 4924892 or 4951601 or 4960140 or 4983223 or 5011542 or 5044871 or 5062770 or 5071485 or 5105556 or 5167716 or 5169296 or 5169408 or 5186718 or 5188515 or 5190373 or 5191993 ).pn.

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7	5	4029517	1977-06 14	Rand	┑		
V	6	4091643	1978-05-30	Zucchini	Ĩ		
V	7	4245154	1981-01-13	Uehara et al.	7		•
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Information Disclosure Statement

Page 3 of 3

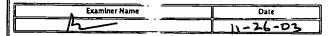
D	40	\$105556	1992-04-21	Kurokawa et al.
$\mathbf{E}$	41	\$167716	1992-12 01	Boltnott et al.
R)	42	5169296	1992-12 08	Wilden
	43	5169408	1992-12-08	Biggerstaff et al.
7	44	5186718	1993-02-16	Tepman et al.
7	45	5188515	1993-02-23	Horn
	46	\$190373	1993-03-02	Dickson et al.
	47	5191993	1993-03-09	Wanger et al.

#### Remarks

Note: Remarks are not for responding to an office action.

Non US Patent and Publication references shall be filed under a separate paper transmittal. The current electronic filing contains part 1 out of a total of 4 electronic filings.

#### Signature



1991-12-10

FORM PTO-1449 (Modified)

(37 CFR § 1.98(b))

**EXAMINER:** 

U.S. Department of Commerce Patent and Trademark Office

Attorney Docket No.: SSI-00501

Serial No.: 09/912,844

INFORMATION DISCLOSURE STATEMENT BY APPLICANT
Use Several Shape if Necessary)

ADEMAN

Applicants: Maximilian A. Biberger et al.

Filing Date: July 24, 2001

Group Art Unit: 1763

		F	OREIGN PATENTS	OR PUBLISHED FOREIGN PATENT APPLICA	TIONS	<del></del>		
		Document Number	Publication Date	Country / Patent Office	Class	Subclass	Trans	lation
		Number	rubication Date	Country / Facility Office	H01L 21/00		Yes	No
	AA	CN 1399790 A	02/26/03	China	HOIL	21/00		X
<u> </u>	AB	DE 36 08 783 A1	09/17/87	Germany	C30B	25/12		<u>x</u>
V	AC	DE 198 60 084 A1	07/06/00	Germany	HOIL	21/3213		х
<b>N</b>	AD	EP 0 244 951 A2	11/11/87	EPO	H01L	21/00		x
~	AE	EP 0 272 141 A2	06/22/88	EPO	HOIL	21/00		x
<u></u>	AF	EP 0 453 867 A1	10/30/91	EPO	F16K	51/02		х
<u>                                   </u>	AG	EP 0 572 913 A1	12/08/93	EPO	B01D	11/02		х
_ <u> </u>	АH	EP 0 587 168 A1	03/16/94	EPO	B08B	7/00		<u>x</u>
~	Ai	EP 0 679 753 B1	11/02/95	EPO	D06F	43/00		x
<u> </u>	AJ	EP 0 903 775 A2	03/24/99	EPO	HOIL	21/00		х
<b>V</b>	AK	FR 1.499.491	09/18/67	France	F16K			x
<u>~</u>	ΑĹ	GB 2 003 975	03/21/79	Great Britain	F04B	43/06		x_
~	AM	GB 2 193 482	02/10/88	Great Britain	B25J	18/02		х
V	AN	JP 2-148841	06/07/90	Japan	H01L	21/306		x
N	AO	JP 2-209729	8/21/90	Japan	H01L	21/302		х
~	AP	JP 11-200035	07/27/99	Japan	C23C	14/34		x
<u>~</u>	AQ	JP 56-142629	11/07/81	Japan	H01L	21/205		х
V	AR	JP 60-238479	11/27/85	Japan	C23C	14/56		х
N	AS	JP 60-246635	12/06/85	Japan	HOIL	21/302		x _
<u> </u>	AT	JP 61-231166	10/15/86	Japan	C23C	14/24		х
٣	AU	JP 62-125619	06/06/87	Japan	H01L	21/30		х
_ v	۸۷	JP 63-303059	12/09/88	Japan	C23C	14/22		х
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<u> </u>	ĄΧ	WO 87/07309	12/03/87	PCT	C23C	16/00		x
~	AY_	WO 00/36635	06/22/00	PCT	H01L	21/00		x
~	AZ	WO 01/55628 A1	08/02/01	PCT	F16K	51/02		x
<u> </u>	BA	WO 01/68279 A2	09/20/01	PCT	B08B	7/00		х
~	ВВ	WO 01/74538 A1	10/11/01	PCT	B24C	1/00		х
~	ВС	WO 01/85391 A2	11/15/01	PCT	B24B			x
<u> </u>	BD	WO 01/94782 A3	12/13/01	PCT	F04B	43/02		x
<u>~</u>	BE	WO 02/16051 A2	02/28/02	PCT	B05D			x
~	BF	WO 03/030219 A2	10/04/03	РСТ	HOIL			х
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Sheet 2 of 2 FORM PTO-1449 (Modified) U.S. Department of Commerce Patent and Trademark Office Attorney Docket No.: SSI-00501 Serial No.: 09/912,844 INFORMATION DISCLOSIFIE STATEMENT BY APPLICANT Sheets If Necessary) Applicants: Maximilian A. Biberger et al. Filing Date: July 24, 2001 Group Art Unit: 1763 (17 CER & 1 98/b)) FOREIGN PATENTS OR PUBLISHED FOREIGN PATENT APPLICATIONS Translation Document Number Publication Date Country / Patent Office Class Subclass Yes No BJ BK BL ВМ BN BO OTHER DOCUMENTS (Including Author, Title, Date, Relevant Pages, Place of Publication) يباه BP Hideaki Itakura et al., "Multi-Chamber Dry Etching System", Solid State Technology, April 1982, pp. 209-214. Sun, Y.P. et al., "Preparation of Polymer-Protected Semiconductor Nanoparticles Through the Rapid Expansion of Supercritical Fluid Solution," Chemical Physics Letters, pp. 585-588, May 22, 1998. BQ lu Dahmen, N. et al., "Supercritical Fluid Extraction of Grinding and Metal Cutting Waste Contaminated with Oils," Supercritical Fluids - Extraction and Pollution Prevention, ACS Symposium Series, Vol. 670, pp. 270-279, 21 Oct 1997. lle RR Xu, C. et al., "Submicron-Sized Spherical Yttrium Oxide Based Phosphors Prepared by Supercritical CO2-Assisted aerosolization and pyrolysis," Appl. Phys. Lett., Vol. 71, No.12, September 22, 1997, pp. 1643-1645. BS Courtecuisse, V.G. et al., "Kinetics of the Titanium Isopropoxide Decomposition in Supercritical Isopropyl Alcohol," Ind. Eng. Chem. Res., Vol. 35, No. 8, pp. 2539-2545, Aug 1996. вт Gallagher-Wetmore, P. et al., "Supercritical Fluid Processing: A New Dry Technique for Photoresist Developing," SPIE Vol. 2438, pp.694-708, Jun. 1995. RL BU el-B۷ Purtell, R, et al., "Precision Parts Cleaning using Supercritical Fluids, "J. Vac, Sci, Technol. A. Vol. 11, No. 4, July 1993, pp. 1696-1701. lh Matson, D.W. et al., "Rapid Expansion of Supercritical Fluid Solutions: Solute Formation of Powders, Thin Films, and Fibers," Ind. Eng. Chem. Res., Vol. 26, No. 11, pp. 2298-2306, 1987. вw Tolley, W.K. et al., "Stripping Organics from Metal and Mineral Surfaces using Supercritical Fluids," Separation Science and Technology, Vol. 22, pp. 1087-1101, 1987. eu ВX eu Joseph L. Foszcz, "Diaphragm Pumps Eliminate Seal Problems", Plant Engineering, pp. 1-5, February 1, 1996. BY Ph ΒZ Bob Agnew, "WILDEN Air-Operated Diaphragm Pumps", Process & Industrial Training Technologies, Inc., 1996. CA СВ CC CD CE CF CG CH CI CJ CK CL

11-26-203 Date Considered: **EXAMINER:** Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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